

PATENT ABSTRACTS OF JAPAN

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(54) CLEANING/DRYING APPARATUS

(57)Abstract:

PROBLEM TO BE SOLVED: To improve the throughput and yield by reducing the entire apparatus for cleaning and drying works.

SOLUTION: An apparatus comprises a cleaning tank 22 for housing a semiconductor wafer W cleaning liq., a drying chamber 23 disposed above the cleaning tank 22, a wafer boat 24 which houses and carries semiconductor wafers W in the cleaning tank 22, a drying chamber 23 composed of a fixed base 37 communicating with an opening 22c of the tank 22, and a drying chamber body 39 contacted to the fixed base 37 through an O-ring 38. The drying chamber body 39 is movable up and down by a first lifting means 44.

